

Boncheol Ku

List of Publications by Year in descending order

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papers

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687363

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1058476

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807
citing authors

#	ARTICLE	IF	CITATIONS
1	Cellulose Nanocrystal Based Bio-Memristor as a Green Artificial Synaptic Device for Neuromorphic Computing Applications. <i>Advanced Materials Technologies</i> , 2022, 7, 2100744.	5.8	29
2	Improved switching and synapse characteristics using PEALD SiO ₂ thin film in Cu/SiO ₂ /ZrO ₂ /Pt device. <i>Applied Surface Science</i> , 2021, 547, 149140.	6.1	12
3	Analog Synaptic Transistor with Al-Doped HfO ₂ Ferroelectric Thin Film. <i>ACS Applied Materials & Interfaces</i> , 2021, 13, 52743-52753.	8.0	37
4	Ar ion plasma surface modification on the heterostructured TaO _x /InGaZnO thin films for flexible memristor synapse. <i>Journal of Alloys and Compounds</i> , 2020, 822, 153625.	5.5	39
5	The coexistence of threshold and memory switching characteristics of ALD HfO ₂ memristor synaptic arrays for energy-efficient neuromorphic computing. <i>Nanoscale</i> , 2020, 12, 14120-14134.	5.6	88
6	Two-terminal artificial synapse with hybrid organic-inorganic perovskite (CH ₃ NH ₃)PbI ₃ and low operating power energy (1/447 fJ/μm ²). <i>Journal of Alloys and Compounds</i> , 2020, 833, 155064.	5.5	41
7	Bio-realistic synaptic characteristics in the cone-shaped ZnO memristive device. <i>NPG Asia Materials</i> , 2019, 11, .	7.9	55
8	Study of in Situ Silver Migration in Amorphous Boron Nitride CBRAM Device. <i>ACS Applied Materials & Interfaces</i> , 2019, 11, 23329-23336.	8.0	52
9	Improved resistive switching and synaptic characteristics using Ar plasma irradiation on the Ti/HfO ₂ interface. <i>Journal of Alloys and Compounds</i> , 2019, 797, 277-283.	5.5	28
10	Compliance-Free, Digital SET and Analog RESET Synaptic Characteristics of Sub-Tantalum Oxide Based Neuromorphic Device. <i>Scientific Reports</i> , 2018, 8, 1228.	3.3	91
11	Interface engineering of ALD HfO ₂ -based RRAM with Ar plasma treatment for reliable and uniform switching behaviors. <i>Journal of Alloys and Compounds</i> , 2018, 735, 1181-1188.	5.5	85
12	Influence of oxygen vacancies in ALD HfO _{2-x} thin films on non-volatile resistive switching phenomena with a Ti/HfO _{2-x} /Pt structure. <i>Applied Surface Science</i> , 2018, 434, 822-830.	6.1	85
13	Structural engineering of tantalum oxide based memristor and its electrical switching responses using rapid thermal annealing. <i>Journal of Alloys and Compounds</i> , 2018, 759, 44-51.	5.5	33
14	Engineering synaptic characteristics of TaO _x /HfO ₂ bi-layered resistive switching device. <i>Nanotechnology</i> , 2018, 29, 415204.	2.6	46